

# Multi-scale model for optimization of low-temperature Al<sub>2</sub>O<sub>3</sub> ALD process conformality within high aspect ratio trench



Fig. 1. ALD reactor model scheme

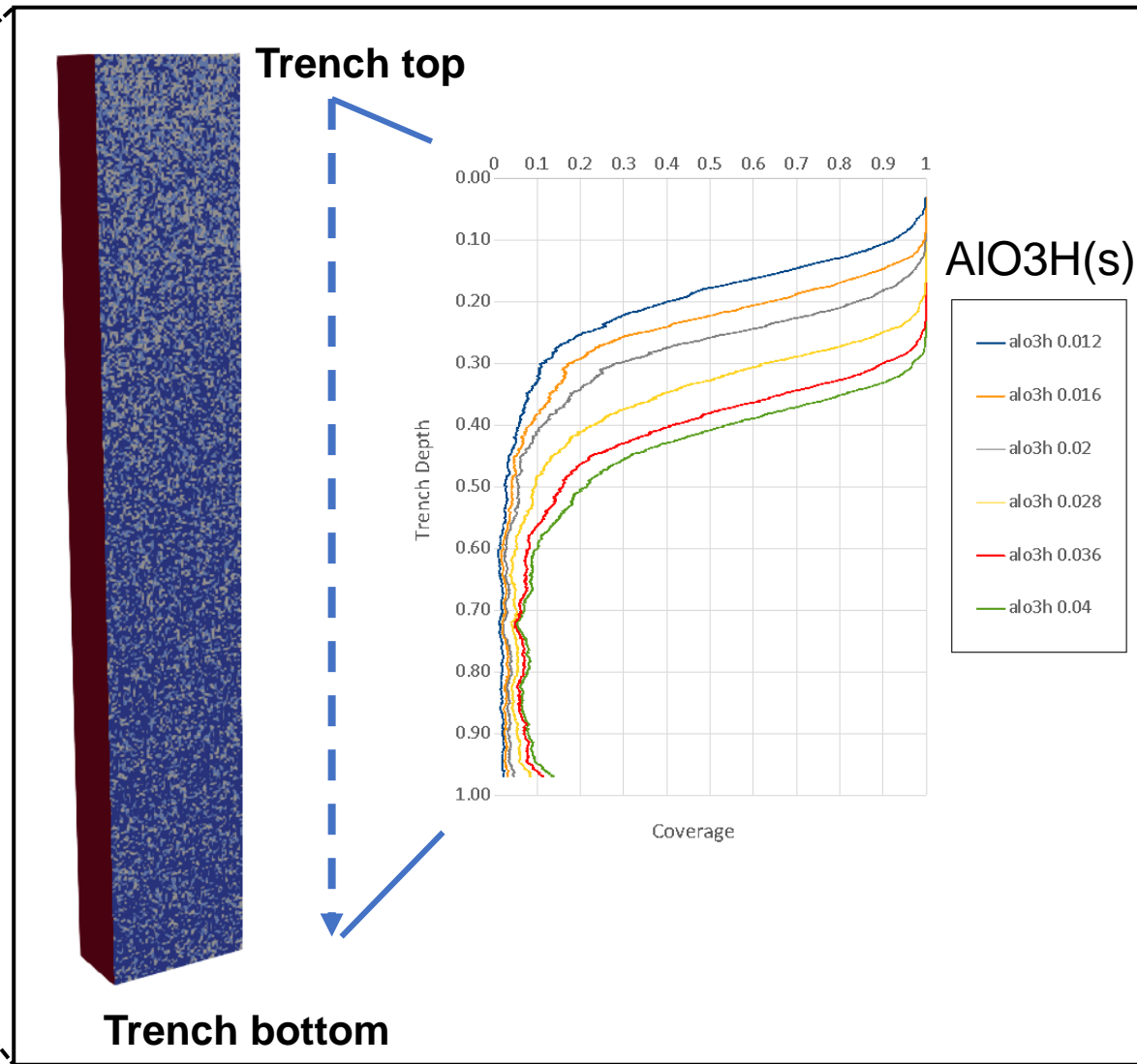


Fig. 2. Example of bad conformality within HAR trench after TMA step

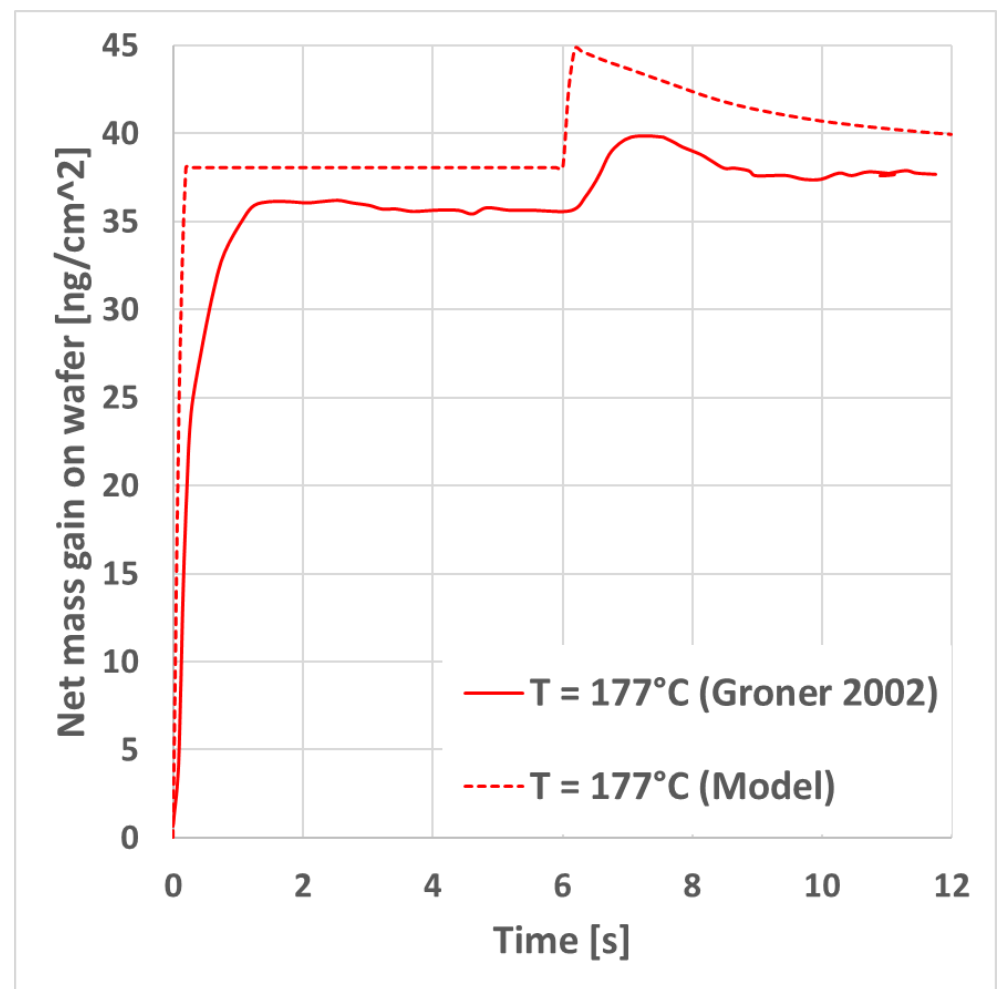
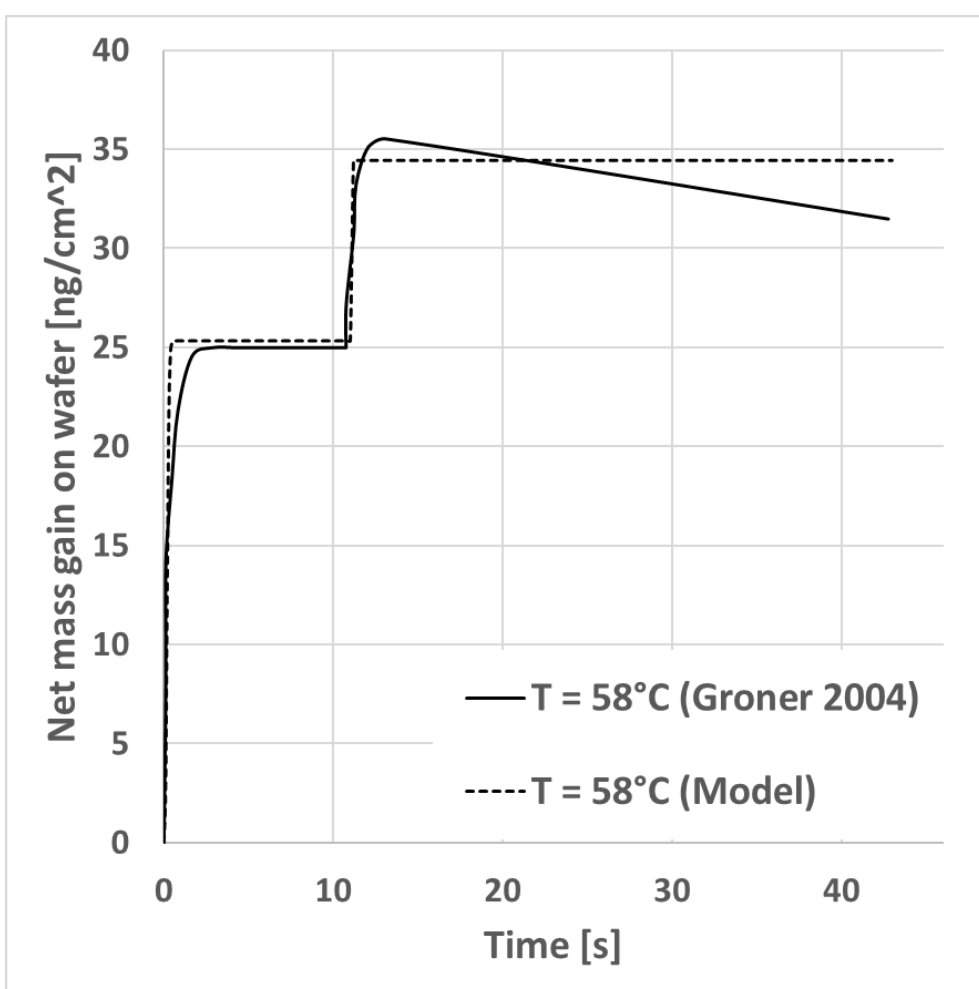


Fig. 3. Wafer mass gain at different temperature